

ABSTRACT

Proposed is a polishing composition including hydroxyethyl cellulose, water and abrasive grains, wherein the hydroxyethyl cellulose has a molecular weight of 500,000 or more and 1,500,000 or less, and the mass ratio of the
5 hydroxyethyl cellulose to the abrasive grains is 0.0075 or more and 0.025 or less.